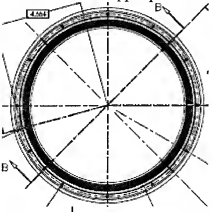

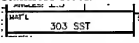



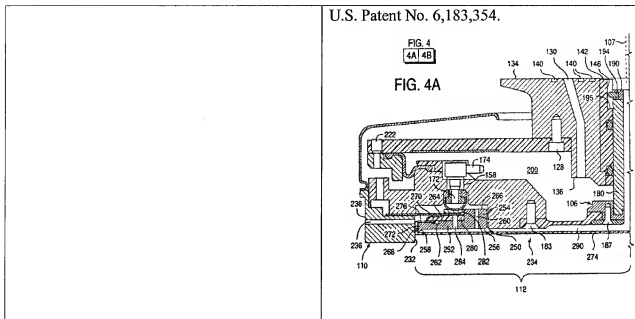
6. On or before December 17, 1997, in the United States, Steven M. Zuniga and Thomas H. Osterheld conceived of a method of assembling a retaining ring. The method includes securing a generally annular lower portion made of a plastic and having a bottom surface for contacting a polishing pad during polishing to a bottom surface of a generally annular upper portion made of a metal which is more rigid than the plastic and having a top surface configured to be mechanically affixed to and about a rigid base of a carrier head.

7. On or before December 17, 1997, in the United States, Steven M. Zuniga and Thomas H. Osterheld conceived of a method of polishing. The method includes holding a substrate on a substrate mounting surface that is vertically movable relative to a base rigid base of a carrier head in a chemical mechanical polishing apparatus, bringing the substrate into contact with a polishing surface, creating relative motion between the polishing surface and the substrate, and maintaining the substrate beneath the substrate mounting surface with a retaining ring. The retaining ring includes a generally annular lower portion having a bottom surface for contacting the polishing surface during polishing, and a generally annular upper portion having a bottom surface joined to the lower portion and a top surface fixed to and abutting the base, and the lower portion is made of a plastic and the upper lower portion is made of a metal which is more rigid than the plastic.

8. As evidence of conception and reduction to practice, Exhibits 1-3 are copies of CAD drawings prepared on or before December 17, 1997 by Steven Zuniga. Exhibit 1 includes a cross-sectional side view showing the upper and lower rings; Exhibit 2 includes a plan view and cross-sectional side view showing the lower ring; and Exhibit 3 includes a plan view and cross-sectional side views showing the upper ring. Exhibit 4 is a copy of a page from a presentation on or before December 17, 1997 in which Steven Zuniga prepared the bullet points. Exhibit 5 is a copy of a page from a presentation on or before December 17, 1997 by Tom Osterheld, the lead process engineer on the "composite ring" project, showing data from testing of the claimed retaining ring.

9. The following table shows the support in the Exhibits for the claimed invention as recited in independent claim 17.

	<p>is a plastic. Exhibit 4, describes a "wear surface", indicating that the bottom surface contacts the polishing pad during polishing</p>
to a bottom surface of a generally annular upper portion	<p>Exhibit 3 shows upper portion as annular.</p>  <p>Exhibit 1, illustrates the bottom surface of the upper ring contacting the lower portion</p> 
made of a metal which is more rigid than the plastic	<p>Exhibit 3 provides that the material of the upper ring is 303 SST. "SST" refers to stainless steel.</p>  <p>Exhibit 4 states "metal backing" Stainless steel is more rigid than polyphenylene sulfide.</p>
and having a top surface configured to be mechanically affixed to and abut a rigid base of a carrier head.	<p>Exhibits 1 and 3 show the top surface of retaining ring.</p>  <p>The complex shape of the top surface was configured to abut a base in the carrier head, e.g., in a manner similar to how the top surface of the completely plastic ring abutted the base in the carrier as shown in Figures 4A-4B of</p>



10. With respect to claim 1, Exhibit 5 shows data, specifically a polishing profile, from test polishing of a wafer using the claimed retaining ring. This testing included holding a substrate on a substrate mounting surface that is vertically movable relative to a base rigid base of a carrier head in a chemical mechanical polishing apparatus, bringing the substrate into contact with a polishing surface, creating relative motion between the polishing surface and the substrate, and maintaining the substrate beneath the substrate mounting surface with the retaining ring.

11. On or before December 17, 1997 a method of assembling a retaining ring having a metal upper portion and a plastic lower portion and a method of a method of polishing with a retaining ring having a metal upper portion and a plastic lower portion were reduced to practice by being performed and tested.

12. As evidence of reduction to practice, Exhibit 4 states “8 prototypes fabricated”. These prototypes included rings meeting the limitations of claim 1. Exhibit 4 further states “Rigid bonded giving good performance”. This refers to testing of the two-part retaining rings.

13. As further evidence of reduction to practice, Exhibit 5 shows data, specifically a polishing profile, from test polishing of a wafer using the claimed retaining ring.

14. The dates in Exhibits 1-5 have been redacted, however all the redacted dates were on or before December 17, 1997.

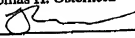
15. We hereby declare that all statements made herein of my own knowledge are true and that all statements made on information and belief are believed to be true; and further that these statements were made with the knowledge that willful false statements and the like so made are punishable by fine or imprisonment, or both, under Section 1001 of Title 18 of the United States Code and that such willful false statements may jeopardize the validity of the application or any patent issued thereon.

Full Name of Inventor: Steven M. Zuniga

Inventor's Signature: 

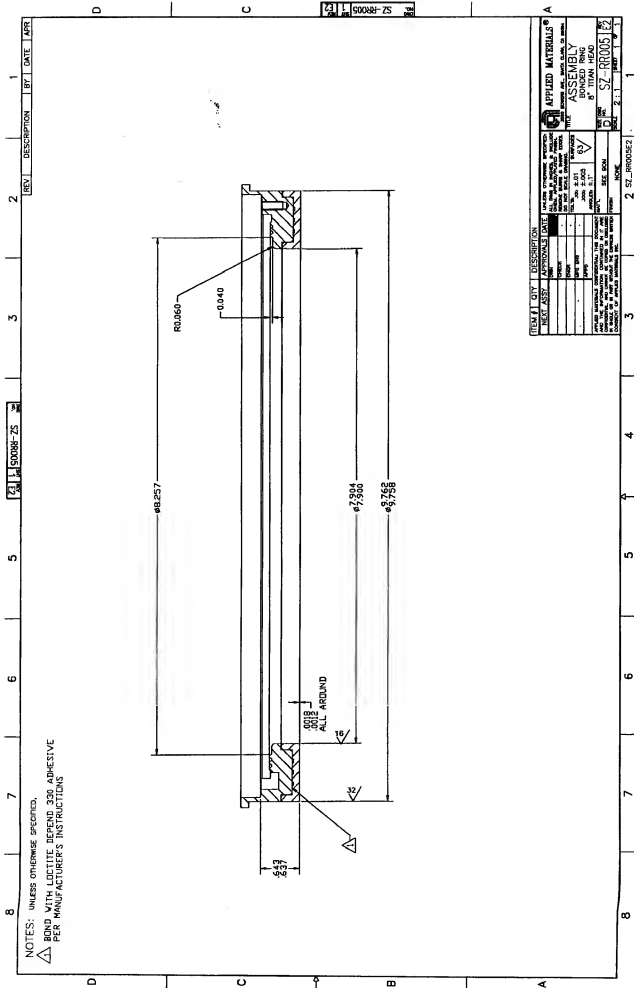
Date: 11/2/2006

Full Name of Inventor: Thomas H. Osterheld

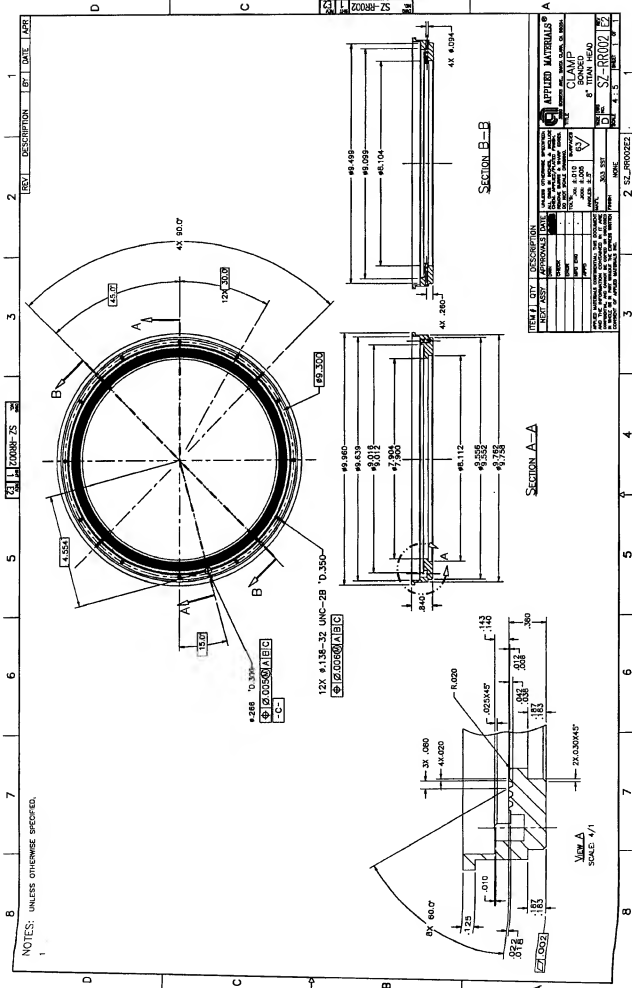
Inventor's Signature: 

Date: 11/2/06

Exhibit 1



Technical drawing of a ring with a cross-section. The drawing includes a top view showing concentric circles and a side view showing the ring's profile. Dimensions are provided in inches. The top view shows an outer diameter of 6.310 and an inner diameter of 6.100. The side view shows a total height of 0.135, with a central core of 0.080 and a surrounding layer of 0.055. A cross-section of the ring is shown with a width of 0.190 and a height of 0.080. The drawing is labeled 'RING' and 'SCALE: 4:1'.

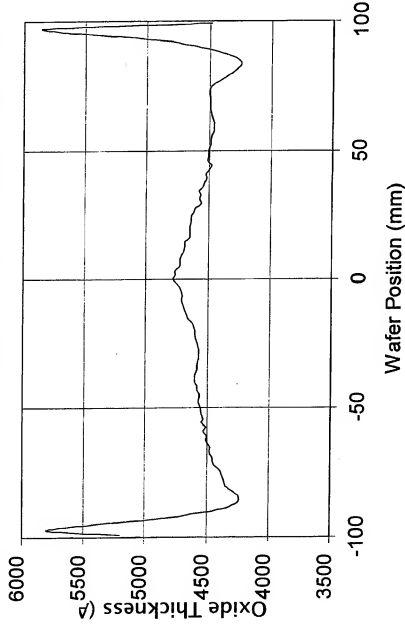


Titan Head Roadmap

- “No Lap” retaining ring #1 priority for CMP group until manufacturable solution is identified. **Goal: Good solution by 10/31. Better solutions may follow.**
 - “No lap” ring development driving understanding of retaining ring: edge exclusion relationship - may result in long term EE improvements
 - ~8 prototypes fabricated
 - Focusing on metal backing with PPS wear surface
 - Rings with “compliance” give poor edge performance
 - Rigid bonded giving good performance - some ring to ring variability still seen in prototypes. Source of variation under investigation
 - “Crowned” PPS ring giving good performance



Stainless Steel/PPS Composite Ring Yields an Edge-Slow Process Under BKM Conditions



Issue: WIWNU Cannot be fixed by Retaining Ring Pressure

OXIDE OPS